# Continuous Emissions Monitoring and Process Control



## Continuous Emissions Monitoring and Process Control in Waste Incinerators

Local authorities incinerate domestic waste and other kinds of waste that typically include plastics, batteries and a diversity of unknown compounds. These may all produce acidic and other toxic emissions. Therefore, efficient flue-gas cleaning systems are needed to prevent their release into the environment.

Acidic compounds are removed by different methods, including wet scrubbers, lime slurry or dry lime injection, the latter being used together with filters such as ESP or fabric filters to trap particulates. In addition, DE-NOX systems and charcoal filters are being increasingly used to satisfy environmental legislation and to minimize general environmental concerns. All flue-gas cleaning methods share a common need for efficient control. This calls for a fast, accurate and cost-effective monitoring system. The system itself clearly needs to withstand the aggressive environment of acidic gases.

#### The Opsis System

Opsis emissions monitoring systems have been designed for such applications. The systems are based on optical monitoring, UV, IR and tuneable laser diode. The technique used is the most suitable for the current application.

#### Performance Data (additional compounds can be monitored)

Compound	Max. measurement range (1 m path) <sup>(1)</sup>	Lowest TÜV approved measurement range	Min. detectable quantities (monitoring path 1 m, measurement time 30 sec.)	Zero drift (1 m path, max. per month) <sup>(6)</sup>	<b>Span drift</b> (per month, better than)	Linearity error (of measure- ment range, better than)	Max. length of fibre optic cable (when monitoring individual compounds) <sup>(5)</sup>	Hardware requirement
AR 600/AR	620 Analyser							
NO <sup>(2)</sup>	0–2000 mg/m <sup>3</sup>	0–150 mg/m <sup>3</sup>	1 mg/m <sup>3</sup>	±2 mg/m <sup>3</sup>	±2%	±1%	10 m	AR 600/620
NO <sub>2</sub>	0–2000 mg/m <sup>3</sup>	0–20 mg/m <sup>3</sup>	1 mg/m <sup>3</sup>	±2 mg/m <sup>3</sup>	±2%	±1%	200 m	AR 600/620
SO <sub>2</sub>	0–5000 mg/m <sup>3</sup>	0–80 mg/m <sup>3</sup>	1 mg/m <sup>3</sup>	±2 mg/m <sup>3</sup>	±2%	±1%	100 m	AR 600/620
NH3 <sup>(3)</sup>	0–1000 mg/m <sup>3</sup>	0–10 mg/m <sup>3</sup>	0.5 mg/m <sup>3</sup>	±1 mg/m <sup>3</sup>	±2%	±1%	10 m	AR 600/620
Hg <sup>(2)</sup>	0–1000 µg/m³	0–150 µg/m³	3 µg/m³	±6 µg/m³	±2%	±1%	50 m	AR 600/620
H <sub>2</sub> O	0–100% Vol.	0–30% Vol.	0.5% Vol.	±1% Vol.	±2%	±1%	100 m	AR 620
HCI	0–10000 mg/m <sup>3</sup>	_	10 mg/m <sup>3 (4)</sup>	±20 mg/m <sup>3 (4)</sup>	±2%	±1%	50 m	AR 620
HF	0–1000 mg/m <sup>3</sup>	_	5 mg/m <sup>3</sup>	±10 mg/m <sup>3</sup>	±2%	±1%	200 m	AR 620
CO <sub>2</sub>	0–100% Vol.	_	0.5% Vol.	±1% Vol.	±2%	±1%	50 m	AR 620
Benzene	0-1000 mg/m <sup>3</sup>	_	1 mg/m <sup>3</sup>	±2 mg/m <sup>3</sup>	±2%	±1%	25 m	AR 600/620
AR 650 Ana	lyser							
HCI	0-5000 mg/m <sup>3</sup>	0–15 mg/m <sup>3</sup>	1 mg/m <sup>3</sup>	±2 mg/m <sup>3</sup>	±2%	±1%	50 m	AR 650
CO	0–10000 mg/m <sup>3</sup>	0–75 mg/m <sup>3</sup>	3 mg/m <sup>3</sup>	±6 mg/m <sup>3</sup>	±2%	±1%	10 m	AR 650
H <sub>2</sub> O	0–100% Vol.	0–30% Vol.	0.1% Vol.	±0.2% Vol.	±2%	±1%	100 m	AR 650
HF	0–1000 mg/m <sup>3</sup>	_	0.2 mg/m <sup>3</sup>	±0.4 mg/m <sup>3</sup>	±2%	±1%	200 m	AR 650
NH <sub>3</sub>	0–1000 mg/m <sup>3</sup>	_	2 mg/m <sup>3</sup>	±4 mg/m <sup>3</sup>	±2%	±1%	200 m	AR 650
N <sub>2</sub> O	0–10000 mg/m <sup>3</sup>	_	10 mg/m <sup>3</sup>	±20 mg/m <sup>3</sup>	±2%	±1%	50 m	AR 650
CH4	0–10000 mg/m <sup>3</sup>	_	5 mg/m <sup>3</sup>	±10 mg/m <sup>3</sup>	±2%	±1%	100 m	AR 650
CO <sub>2</sub>	0–100% Vol.	—	0.1% Vol.	±0.2% Vol.	±2%	±1%	50 m	AR 650
LD 500 Laser Diode Gas Analyser								
HCI	0-5000 mg/m <sup>3</sup>	_	0.5 mg/m <sup>3</sup>	±1 mg/m <sup>3</sup>	±2%	±1%	500 m*	LD 500
CO	0–100% Vol.	_	0.1% Vol.	±0.2% Vol.	±2%	±1%	500 m*	LD 500
H <sub>2</sub> O	0–100% Vol.	_	0.1% Vol.	±0.2% Vol.	±2%	±1%	500 m*	LD 500
HF	0–5000 mg/m <sup>3</sup>	_	0.05 mg/m <sup>3</sup>	±0.1 mg/m <sup>3</sup>	±2%	±1%	500 m*	LD 500
NH <sub>3</sub>	0–5000 mg/m <sup>3</sup>	_	0.5 mg/m <sup>3</sup>	±1 mg/m <sup>3</sup>	±2%	±1%	500 m*	LD 500
CO <sub>2</sub>	0–100 g/m <sup>3</sup>	_	0.1% Vol.	±0.2% Vol.	±2%	±1%	500 m*	LD 500
O <sub>2</sub>	0-21%	_	0.1% Vol.	±0.2% Vol.	±2%	±1%	500 m*	LD 500
Temperature	0–1400°C	—	5°C	±10°C	±2%	±1%	500 m*	LD 500

(1) This data refers to a light path of 1 m. For longer paths the maximum range is proportionally smaller. Products are available to create shorter paths in very wide stacks. For other ranges, please contact your local Opsis representative.

<sup>(5)</sup> When monitoring several compounds, the shortest fibre optic cable given by the set of components (refer to product sheet P9) has to be used.

<sup>(6)</sup> For AR 650 the same values are valid as maximum zero drift per year

<sup>(2)</sup> Maximum SO<sub>2</sub> concentration 5 g/m<sup>3</sup> × m. <sup>(3)</sup> Maximum SO<sub>2</sub> concentration 500 mg/m<sup>3</sup> × m

(4) Monitoring path 5 m, measurement time 30 seconds.

\* Laser and communication cables.

Recommended monitoring path length: 1 to 5 m.
After wet scrubbers or when particulate concentration averaged over one metre is higher than 5 g/m<sup>3</sup>, the monitoring path length may have to be reduced.

Using DOAS (Differential Optical Absorption Spectroscopy) provides an open-path, non-contact monitoring system unaffected by the gases, temperatures and particulate matters typical of stack conditions. The ability of monitoring a range of user-specified compounds continuously in real time with a single system, offers fast response needed for process control.

As an example, with SCR and SNCR processes, Opsis is used for the continuous monitoring of nitric oxide (NO), nitrogen dioxide (NO<sub>2</sub>) and ammonia (NH<sub>3</sub>) in both clean and raw gas and for controlling the NH<sub>3</sub>/ urea dosage. Another example is the monitoring of sulphur dioxide (SO<sub>2</sub>), hydrogen chloride (HCl), mercury (Hg) and hydrogen fluoride (HF) before and after scrubbers used for processes controlling lime dosage.

A single Opsis system will operate several monitoring paths, making before-and-after monitoring with one single system very cost-effective.

Among other compounds, Opsis can be specified to monitor carbon dioxide  $(CO_2)$  and water vapour  $(H_2O)$ , where data is commonly required as part of an emissions control process. The LD 500 laser diode analyser



An Opsis laser diode system layout



An Opsis DOAS system layout for a waste incineration plant

can be used to monitor  $O_2$  and temperature. Also, it can be used for monitoring explosive levels of CO for filter control.

In addition, Opsis offers dilution extractive and heated extractive systems as well as a portable mercury monitor for detecting Hg total and Hg atomic.

#### The Opsis Technique

An Opsis system includes one or several light paths crossing the stacks or ducts. In each path, light is projected from an emitter to a receiver. It is then transmitted to the Opsis analyser via a fibre optic cable. Using Beer Lambert's Law, the analyser then detects and measures compounds specified in the system software and logs data to a hard disk, either in a local or remote PC. This computer may act as a real-time display or, when required, run a data presentation and reporting software.

The Opsis analyser will also accept continuous data

from sensors monitoring process variables such as temperature, pressure and flow (4 to 20 mA or digital input). This, combined with the system's ability to provide alarm outputs and/or interface with other plant systems via serial communication, allows Opsis to operate as a process control system. Integrating sensor and measurement data in Opsis software also allows the automatic calculation and generation of reports meeting legislative requirements.

#### Tests and Approvals

Opsis has been tested and approved by a number of internationally recognized institutes and authorities. The system meets the U.S. EPA requirements, 40 CFR Parts 60 and 75, and the German TÜV requirements. Full details are available on request.

Please contact your Opsis supplier to discuss your particular system requirements, including the compounds you wish to monitor. Separate product and other industrial application sheets are available. *Specifications subject to change without notice* 

### **Continuous Emissions Monitoring and Process Control**

### Why Opsis?

High-performance, cross-stack monitoring Multi-gas and multi-path system Combines the benefits of UV, IR and TDL technology No sample required High-quality instruments for operation in harsh environment Operates with a minimum of maintenance Easily calibrated Internationally approved Hundreds of systems installed worldwide Serviced by highly skilled service network

Opsis AB, Box 244 SE-244 02 Furulund Sweden Telephone Int +46 46 72 25 00 Telefax Int +46 46 72 25 01 E-mail info@opsis.se URL http://www.opsis.se

2001 12

**A1**